



# High Accuracy printed electronics down to $\mu\text{m}$ size, for Organic Large Area Electronics (OLAE) Thin Film Transistor (TFT) and Display Applications

H2020-DT-NMBP-18-2019

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## PUBLIC SUMMARY OF Deliverable Report: D6.2 Fabrication of rigid test structure for QD performance testing including public summary

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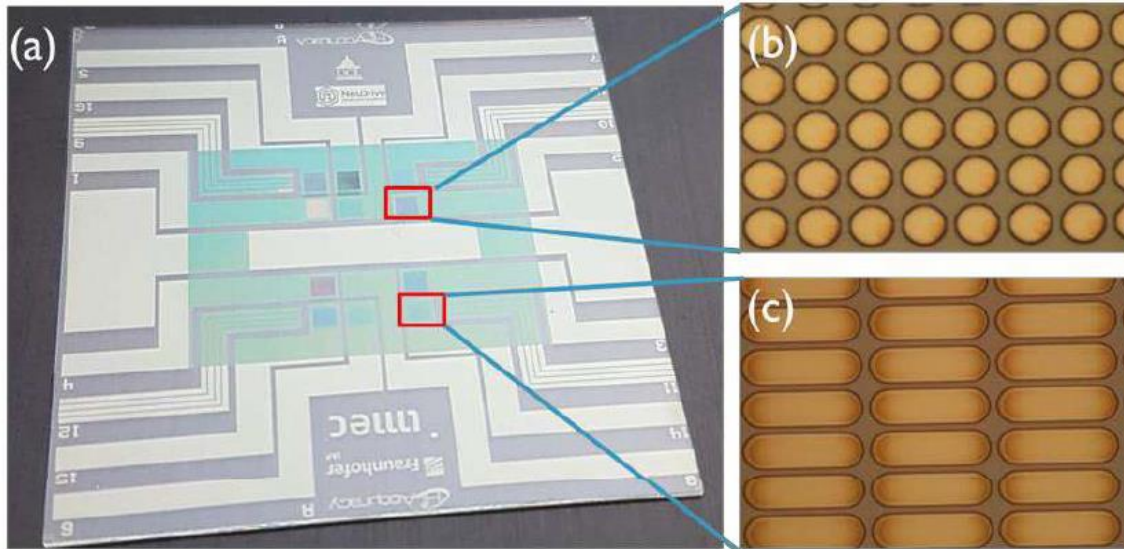
Prepared by: TungHuei Ke, Oliver Buchan

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Dissemination level		
<b>PU</b>	Public	X
<b>CO</b>	Confidential, only for members of the consortium (including the Commission Services)	

## 1 PUBLIC SUMMARY

In order to verify QD-LED fabrication by ESJET printing, we designed (imec) and fabricated (Neudrive) a test substrate variation in shape (circle, superellipse), pixel definition (338 ppi to 3175 ppi), and aperture ratio (12 % to 75%) for IAP to develop a QD-LED fabrication processes by ESJET printing.



**Figure 1.** (a) The fabricated rigid glass substrate for QD-LED ESJET printing process development. (b) The zoom-in of active area with circle PDL opening (c) The zoom-in of active area with superellipse PDL opening